

**AMENDMENTS TO THE SPECIFICATION**

Following the title, please insert the following paragraphs:

**Cross-Reference to Prior Application**

This is a U.S. National Phase Application under 35 U.S.C. §371 of International Patent Application No. PCT/JP2004/017672 filed November 22, 2004, and claims the benefit of Japanese Patent Application No. 2003-422354 filed December 19, 2003 and Japanese Patent Application No. 2004-264196 filed September 10, 2004 all of which are incorporated by reference herein. The International Application was published in Japanese on July 7, 2005 as WO 2005/062083 A1 under PCT Article 21(2).


Please replace the paragraph beginning on page 9, line 12, with the following rewritten paragraph:

-- Figs. 1A to 1C is are a simplified cross-section drawings illustrating a method for making a refraction microlens array according to an embodiment of the present invention. --

Please replace the paragraph beginning on page 9, line 15, with the following rewritten paragraph:

-- Figs. 2A to 2D is are a simplified cross-section drawings illustrating a method for forming an imprint mold that can be used in the method for making a refraction microlens array shown in Fig. 1. --

Please replace the paragraph beginning on page 9, line 21, with the following rewritten paragraph:

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-- Figs. 4A and 4B is are a simplified cross-section drawings illustrating an example of a method for making a diffraction microlens shown in Fig. 3. --

Please replace the paragraph beginning on page 10, line 3, with the following rewritten paragraph:

-- Figs. 6A to 6C is are a simplified cross-section drawings showing a method for making a refraction microlens array shown in Fig. 5. --

Please replace the paragraph beginning on page 10, line 5, with the following rewritten paragraph:

-- Figs. 7A to 7F is are a simplified cross-section drawings showing a method for making a conventional relief-type diffraction microlens. --

Please replace the paragraph beginning on page 10, line 7, with the following rewritten paragraph:

-- Figs. 8A and 8B is are a simplified plan drawings showing a mask used in a method for making a relief microlens shown in Fig. 7. --